

平成 19 年度第 4 回 VBL セミナー

(4th VBL Seminar, 2007)

日時： 平成 19 年 11 月 22 日(木) 13 時 30 分～15 時 00 分

場所： 名古屋大学フロンティアプラザ (VBL) 4 階セミナー室

Date: Thursday 22, November 2007, 13:30-15:00

Place: Seminar room, 4th floor, Frontier Plaza (VBL)

Title: Growth of III-Nitride Semiconductors by Mixed-Source Hydride Vapor Phase Epitaxy

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We performed the growth of III-nitride semiconductors by the mixed-source hydride vapor phase epitaxy (HVPE) method in which the metal-chlorides were formed by the reaction of HCl gas with mixed form of group III metals. For the growth of AlGa_N layers, mixed form of gallium (Ga) and aluminum (Al) metals were used for the reaction of metal-chloride sources. We could control the Al composition of the AlGa_N layers from 0.6% to 80% by the variation of source zone temperature. For the growth of conductive III-nitride semiconductors, tellurium (Te) was used as n-type doping material in Ga_N and AlGa_N layers in the mixed-source HVPE. For the case of Ga_N layers, the maximum carrier concentration was $8 \times 10^{18} \text{cm}^{-3}$. Mixed form of indium (In) and gallium (Ga) metals were used as metal-chloride sources for the growth of InGa_N layers. Optical properties of the InGa_N layers were investigated by cathodoluminescence (CL) measurement. We fabricated non-phosphor white LED structures which have InAlGa_N active layers by using of multi-bin sliding graphite boat in the mixed-source HVPE system. With the addition of indium into the AlGa_N active layers, the electroluminescence (EL) spectrum became broadened over the whole visible range. We could also make InGa_N micro-structures by the mixed-source HVPE on sapphire and silicon substrates. The size and shapes of the InGa_N micro-structures were dependent on growth temperature. Especially for the case of r-plane sapphire, nano-sized hexagonal pillars could be obtained.

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